Maharaja Surajmal Institute of Technology

Applied Sciences Department

FDP Report

Topic: SILICON AND CARBON BASED MATERIAL

Department of Applied Sciences, MSIT, organized a Faculty Development Programme on "SILICON AND CARBON BASED MATERIAL" on 27th February,2016 (Saturday). The Chief guest and the key speaker of the FDP was Prof.(Dr.) O.S.Panwar, working with Advanced Materials and Devices Group,Physics of Energy Harvesting Division, CSIR-National Physical Laboratory, New Delhi-110012.The function started with the welcome note by Dr. Jindagi Kumari followed by the floral welcome of the chief guest by Dr. Pooja Singh.All faculty members attended the FDP. Prof.(Dr.)B.S.Panwar in his speech talked about the techniques generally used in vacuum evaporation, Sputtering, Ion beam and Ion assisted deposition, Reactive deposition techniques, Chemical method of film deposition (CVD), Other Methods like Epitaxy method (LPE, MBE, HWE), Langmuir Blodgett method,Spray hydrolysis , spray pyrolysis, spray method, Ionized cluster beam method. e) Electron deposition.The eminent speaker also talked about the properties of Carbon & Silicon.He told about the plasma process of NPL i.e. the most suitable process to deposit the various nanostructured thin films, e.g. Si, nC-Si, SiO_2, carbon nanotubes, nanodiamond etc.

The lecture ended with interactive session with the faculty. The programme concluded with thanks giving by Dr. Jindagi Kumari and the presentation of a momento to the chief guest by Dr. Poonam Bansal.

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